

THE EFFECTS OF DEPOSITION AND ANNEALING TEMPERATURE AND TIME ON THE OPTICAL AND SOLID STATE PROPERTIES OF CADMIUM SELENIDE (CdSe) THIN FILMS GROWN BY CHEMICAL BATH DEPOSITION TECHNIQUE

S.M.U. ISHIWU*, M.N. NNABUCHI, C.N. EZE^a

Department of Industrial Physics, Ebonyi State University, Abakikili – Nigeria.

^aCentre for Environmental Management and Control (CEMAC) University of Nigeria, Enugu Campus (UNNEC).

Two groups of cadmium selenide thin films (One group deposited at room temperature of 25°C, the second group deposited at 74°C) were deposited on glass substrate by chemical bath deposition. A moderately stable sodium selenosulphite (Na₂SeSO₃) was used as a source of Se²⁻ ions. To prevent spontaneous precipitation and ensure ion-by-ion deposition on the substrate, TEA was used as a complexing agent. The structural nature was obtained from X-ray diffraction (XRD) analysis. The optical properties were obtained from absorption and transmittance data within the range of 200-to-1000nm. To know the effect of deposition and annealing temperature on the optical and solid state properties of the films; some were deposited at room temperature (25°C), some at 74°C while some were annealed at different temperatures, the rest were not annealed. Some of the films were found to have a good transmittance and low reflectance hence suitable for window coatings for cold climates and antireflection coatings.

(Received January 13, 2011; accepted January 31, 2011)

Keywords: Deposition and annealing temperature and time, optical and solid state, Chemical Bath Technique, Cadmium Selenide thin films,

1. Introduction

The grown CdSe thin films have been extensively studied due to their variety of applications in optoelectronic devices. Owing to its optical and structural properties, CdSe is used as an optical window (Udeaja, 1996). However, poor absorption and reflectance has been reported and in an effort to discover the cause and overcome this problem, deposition was done at both room and higher temperatures, different annealing temperatures were also used in this work. The deposited CdSe are semiconductors.

Several methods such as: pyrolysis (Kosugi et al, 1998), hot-wall epitaxy (HWE) (Huber, 1979 & Sitter et al, 1988). Cathodic sputtering (Grove, 1852), Electrochemical deposition (Nelkon, 1985 & Awe et al, 1984) has been used in deposition of thin films, but for good quality film suitable for use as selectively absorbing surfaces as those of cadmium selenide, high temperature techniques (>900°C) are unsuitable since this can cause rapid oxidation and contamination by environmental gases. Information from literature showed that CdSe thin films with a band gap of 1.8 eV has been grown using solution growth technique (Mondal et al. 1983) also a grown CdSe with a band gap range of 1.45 - 1.98 eV has been reported (Osuji 1994). Categorically, good quality CdSe should be reddish brown or yellowish brown in colour with high transmittance within visible (VIS) and near infra-red (NIR) ranges and low absorbance towards IR. This makes it suitable for solar cell application.

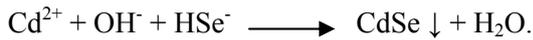
We present in this paper the procedure for preparing Cadmium selenide thin films using the chemical bath techniques, which is simple, less expensive in chemical and equipment and most

*Corresponding author: ishiwusmu@gmail.com

suitable for control experiments. Since spontaneous precipitation affects both structural and optical qualities, a complexing agent and buffer solution that control the PH were used to ensure high quality thin films that enhance the study of effects of deposition and annealing temperatures on the properties of thin films.

2. Experimental details

Cadmium Selenide thin films were produced using chemical bath deposition technique. In the deposition, the reaction bath was made up of solution of 5ml of 1M cadmium acetate $(\text{CH}_3\text{COO})_2\text{Cd}\cdot 2\text{H}_2\text{O}$, 4ml of 1M sodium selenosulphite $(\text{Na}_2\text{SeSO}_3)$, 5ml of 13.4M ammonia solution (NH_3) , 10ml of 7.4M triethanolamine (TEA) $[\text{N}(\text{CH}_2\text{CH}_2\text{OH})_3]$ as complexing agent and 40 ml of distilled water. Seven reaction baths of these films were prepared. The dissociation relation and the equation for the chemical reactions are:



Seven reaction baths of these films were prepared and the detail of the molar and volume concentration of the reagents as well as the times and temperature of the various reaction baths are displayed in Table 1 below.

The reaction baths were thoroughly stirred with glass rod instead of the magnetic stirrers to ensure uniform deposition since it was observed that constant stirring with magnetic stirrers during the process of deposition did not allow films to deposit. Glass slides of 76mm x 26mm x 1mm were used as substrates and synthetic foam covers were used not only to protect the reaction bath from environmental impurities but also to support the substrate instead of clamping them into open baths. The experiments were carried out under both room temperature (25°C) and at (74°C) respectively.

The thin films were annealed at different temperatures for one hour each. The optical characterization of the thin films was done using the single beam scanning spectrophotometer from the ultraviolet (UV), through the visible (VIS) to the near infrared (NIR) region of the electromagnetic spectrum. The surface structural analysis was undertaken with a photomicroscope attached to a camera set an objective magnification of X200. The composition analysis of the samples was done using X-ray photoelectron spectroscopy. The optical parameters were estimated from the absorbance and transmittance data while the thickness and band gap were obtained using optical techniques.

Fig1a, 1b and 1c are the plotted graphs of absorbance, transmittance and reflectance versus wavelength of the film samples. Fig2a shows the plot of $(\alpha \text{ hv})^2$ Vs (hv) for CdSe. Considering the absorption edges, which are characteristics of the crystalline state of the films, the fundamental absorption which corresponds to the electron excitation from the valence band to the conduction band, was used to determine the value of the optical band gap. The relationship between the absorption coefficient (α) and the incident photon energy (hv) can be written as:

$$(\alpha \text{ hv})^{1/2} = A (\text{hv} - E_g).$$

Where A = constant, E_g = band gap, n = transition type whose value may be $1/2$, 2 and $3/2$ for direct allowed, indirect allowed and direct forbidden transition respectively. However, using Tanc's plot of $(\alpha \text{ hv})^2$ Vs (hv) , the photon energy at the point where $(\alpha \text{ hv})^2$ is zero represents E_g , which is determined by extrapolation shown in Figure 2a (with the value of ' α ' determined from

transmittance spectral) [Pankove 1971, (Tauc, 1970)]. The grain sizes of the films were obtained using Debye Scherer relation:

$$D = \frac{K\gamma}{\beta \cos \phi}$$

Where $k = 0.94$, $\lambda = X\text{-ray wavelength} = 1.54 \text{ \AA}$, β is the full width half maximum of the obtained pulse of XRD diffractograms. ϕ is the Bragg's angle.

3. Results and discussion

The spectral absorbance and optical transmittance, reflectance and band gap of Cadmium selenide films are displaced in figure: 1, 2 and 3. Fig.1 presents the samples: Cd(7) showed peak absorbance at UV regions of 340 – 400 with peak value of 0.9 and 0.85 while sample Cd(2) and Cd(5) showed a uniform absorbance of about 0.80 and 0.70 in the range of 340 – 640 nm after which absorbance decreased uniformly. The poorest absorbance was exhibited by sample Cd(1). Transmittance was shown in Fig.2 to be the inverse of absorbance with the sample Cd(1) having the highest transmittance of about 92% transmittance in the range of 540 – 1000 nm. All the thin films had relatively low reflectance of approximately 20% shown in Fig.3. It was equally shown that increase in the annealing temperature increases reflectance and absorbance but decreases transmittance. With the above properties of low reflectance and high transmittance the films are good materials for thermal control window which is coatings for cold climates and antireflection coatings. Generally, those deposited at room temperature (25°C) have higher band gap value when compared with those at 74°C. It was observed that minimum band gaps of the two groups occurred at annealing temperature of 100°C while the maximum band gaps (2.12 and 2.55) of the groups were observed on unannealed (as-deposited) samples of Cd(4) and Cd(1). Finally, table 1 shows that as the annealing temperature increases above 100°C, the band gap increases. This may be attributed to possible reaction with some gases in the annealing oven (or sintering chamber). The average crystal size of the film was 2.6 Å or 26 nm. The band edge sharpness reduces with annealing temperature due to the reorganization of the films and filling of the voids as water contents evaporates (Erat, et al, 2007). Results from literature showed that different range of CdSe band gaps produced through CBD includes: 1.7-1.83 eV (Erat, 2007), 1.7 eV (Pujari, 2001), 1.8-3.2 eV (Udejaja, 1996). Hence when compared with these in literature, the obtained band gaps are in compliance with the already existing values elsewhere, (Rincon, 1998).

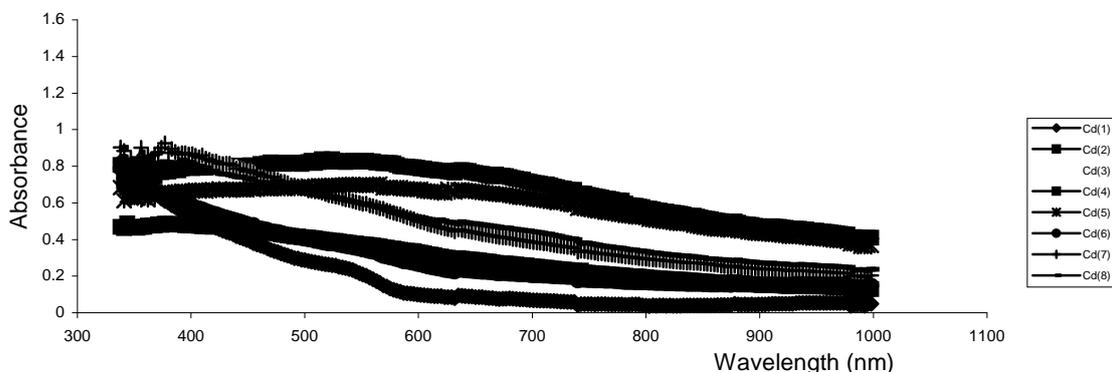


Fig: 1 Absorbance vs wavelength for CdSe

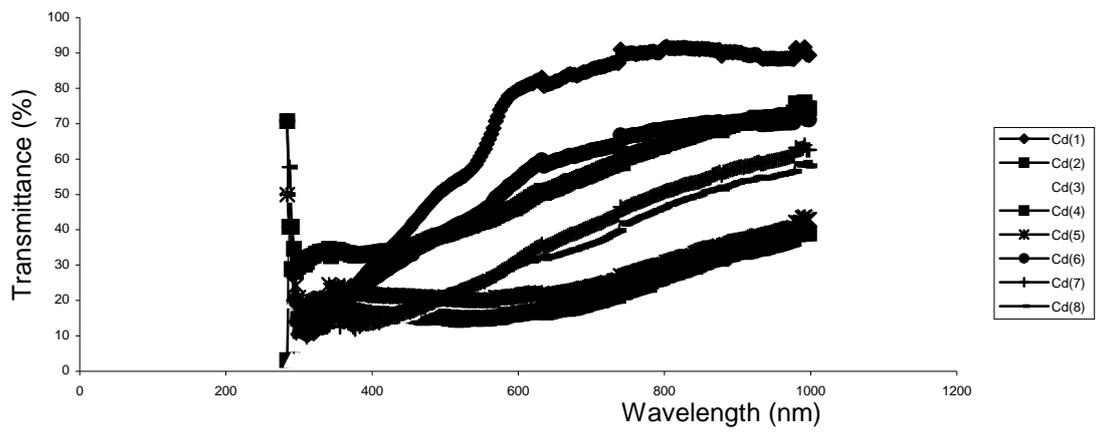


Fig: 2 Transmittance vs. wavelength for CdSe

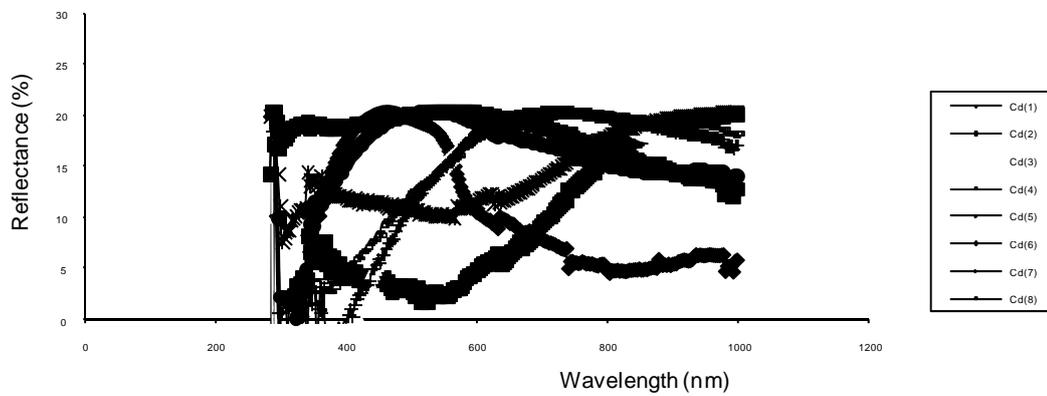


Fig: 3 Reflectance vs. wavelength for CdSe

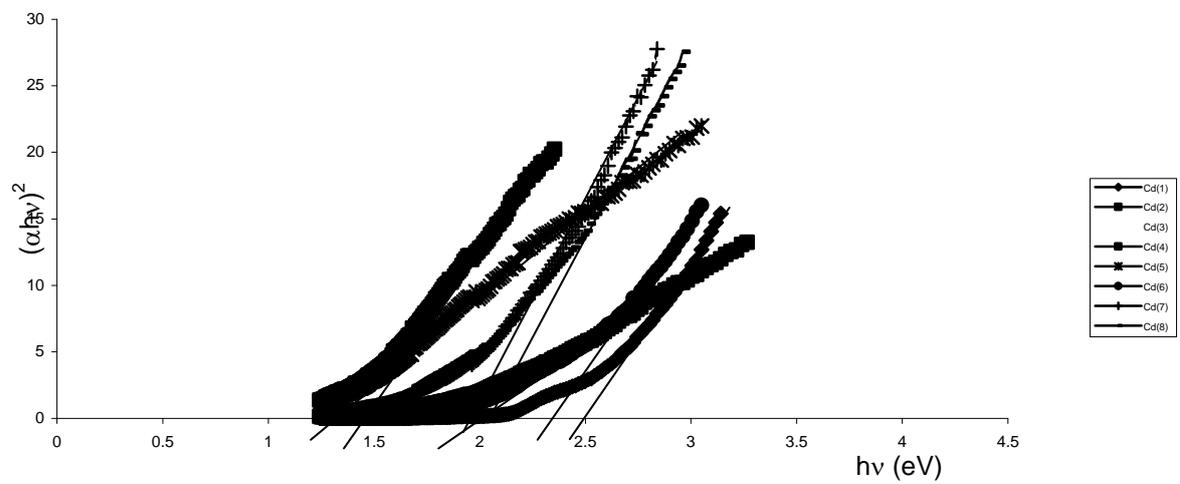


Fig: 3b Plot of $(\alpha hv)^2$ vs. $h\nu$ for CdSe

Table 1: Summary of the band gaps of the grown films.

| S/NO | CdSe film | Band gap hv (eV) | Annealing temp.(°C) | Diptime (hrs) | Deposition temp.(°C) |
|------|-----------|------------------|---------------------|----------------|----------------------|
| 1. | Cd (1) | 2.55 | 0 | 24 | 25 |
| 2. | Cd (2) | 1.35 | 100 | 4 | 74 |
| 3. | Cd (3) | 2.10 | 300 | 4 | 74 |
| 4. | Cd (4) | 2.12 | 0 | 4 | 74 |
| 5. | Cd (5) | 1.28 | 100 | 24 | 25 |
| 6. | Cd (6) | 2.28 | 300 | 24 | 25 |
| 7. | Cd (7) | 2.10 | 200 | 4 | 74 |

It was found that the deposition temperature has no effect on these films but they were affected by deposition time (diptime), causing higher thickness.

Typical XRD pattern displayed in fig.4b shows several peaks at 2θ of 19.38, 19.78, 34.36, 47.18 and 66.63. Cadmium sample Cd(2) presents one of the most outstanding peaks with almost a single peak at 2θ around 20.36. This suggests a compound crystal whose over 90% volume is made of a single element leaving the rest of the elements as trace.

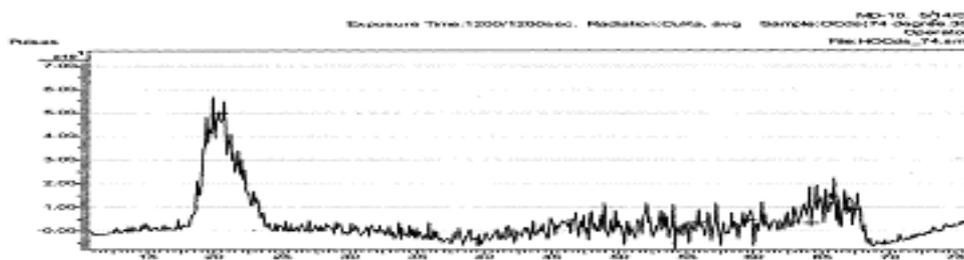


Fig.4a: XRD result of Cd(4)

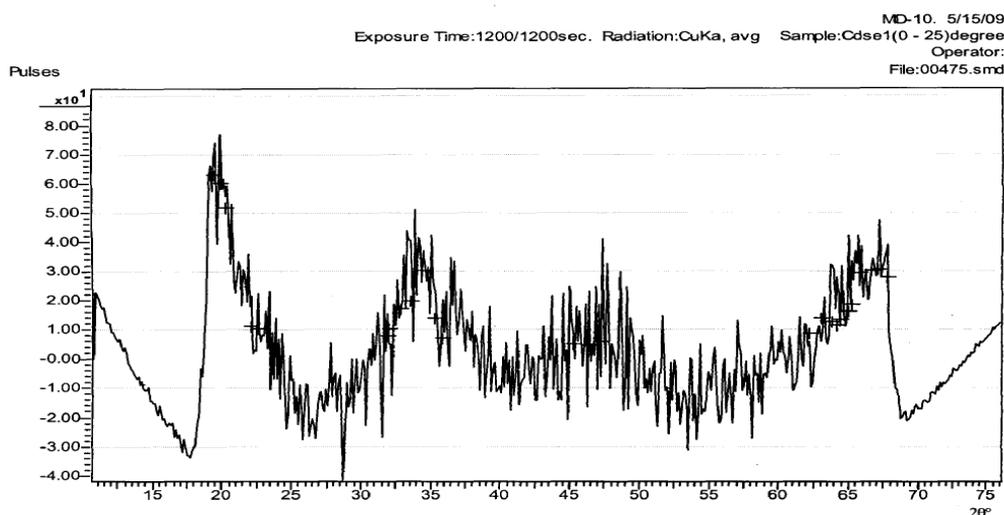


Fig4b: XRD result of Cd(1)

4. Conclusions

The deposition of CdSe thin films has been successfully carried out in alkaline medium using chemical bath deposition techniques. The results obtained from the spectrophotometers shows that the peak values of “n” ranged between 1.10 and 2.35, the grain size of the films ranged between 1.14 Å and 2.60 Å, and the band gap ranged between 2.55 and 1.28 eV. The films were found to have a good transmittance of which, one reached, up to 92% in the VIS-NIR regions. These results show that the films could be used for window coatings for cold climates and antireflection coatings. It was found that the optical and solid state properties of CdSe thin films are functions of their deposition time and annealing temperatures but independent of the deposition temperature.

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